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PATENT
2224-0163P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Tatsuya NAKANO Conf.: 5816
Appl. No.: 09/463,059 Group: 1752
Filed: January 19, 2000 Examiner: THORNTON
For: ACID-SENSITIVE COMPOUND AND RESIN
COMPOSITION FOR PHOTORESIST

22/2

RCE AMENDMENT

March 13, 2003

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

Prior to continued examination on the merits, please enter the following amendments and remarks into the file of the above-identified application.

IN THE CLAIMS:

Cancel claims 5-7, without disclaimer or prejudice.

Amend claims 1, 2, 8, 10, 13, and 14 -- and add new claims 15 and 16 --
so that the claims herein read:

1. (four times amended) An acid-responsive compound represented by the
following formulae (1a-1) or (1a-2)

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